L Number	Hits	Search Text	DB ·	Time stamp
1	2	jp-2000035665-\$.did.	USPAT;	2003/07/09 08:57
	_	Jp 2000035005 Q.u.a.	US-PGPUB;	
			EPO; JPO;	
[			DERWENT	
[ -	2	(("20020068237") or ("20020068236")).PN.	US-PGPUB	2003/07/09 08:57
-	1975440	resin resist photoresist	USPAT;	2003/07/07 12:06
		-	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	16077	(photoacid acid) near generat\$3	USPAT;	2003/07/07 12:06
,			US-PGPUB;	
			EPO; JPO;	]
			DERWENT	1
-	78586	<del>*</del>	USPAT;	2003/07/07 12:05
		C 1 (C)	US-PGPUB;	
		Past seuron	EPO; JPO;	
	1000314		DERWENT	2002/07/02 12 46
-	1008314	East search	USPAT;	2003/07/03 13:46
			US-PGPUB; EPO; JPO;	
_	1234	(resin resist photoresist) and ((photoacid	DERWENT USPAT;	2003/07/03 13:49
-	1234	acid) near generat\$3) and (photosensitizer	US-PGPUB;	2003/07/03 13:49
		sensitizer ) and solvent	EPO; JPO;	
		Scholelzer / and Bolvene	DERWENT	
_	5890	benzopyran	USPAT;	2003/07/07 12:06
	2020		US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	25	((resin resist photoresist) and ((photoacid	USPAT;	2003/07/07 11:40
		acid) near generat\$3) and (photosensitizer	US-PGPUB;	
		sensitizer ) and solvent) and benzopyran	EPO; JPO;	
		••	DERWENT	
-	155	IMAI-G IMAI-GENICHI IMAI-GENJI	USPAT;	2003/07/08 16:22
1			US-PGPUB;	
ŀ			EPO; JPO;	
		,	DERWENT	
-	6	,	USPAT;	2003/07/07 12:01
		benzopyran	US-PGPUB;	
		1	EPO; JPO;	
			DERWENT	2222/22/22 22 22
-	78586	photosensitizer sensitizer	USPAT;	2003/07/07 12:06
		12 A/MT 1/0 MINO	US-PGPUB;	
	$\sim$ 1	I Y) NO I KUTOVEZ	EPO; JPO; DERWENT	
	_ <u> </u>	hongonyman	USPAT;	2003/07/07 12:06
-	2020	benzopyran	US-PGPUB;	2003/07/07 12:06
			EPO; JPO;	
			DERWENT	.
_	61	(photosensitizer sensitizer ) same	USPAT;	2003/07/07 12:08
	01	benzopyran	US-PGPUB;	====, =,, =, ====
		F 1	EPO; JPO;	
			DERWENT	
_	16077	(photoacid acid) near generat\$3	USPAT;	2003/07/07 17:04
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	1975440	resin resist photoresist	USPAT;	2003/07/07 12:06
ĺ			US-PGPUB;	
ĺ			EPO; JPO;	
	_ i	//	DERWENT	2002/05/25 25 25
-	7	, . <u>F</u>	USPAT;	2003/07/07 12:07
		benzopyran ) and ((photoacid acid) near	US-PGPUB;	
ľ		generat\$3 ) and (resin resist photoresist )	EPO; JPO;	
	۾ ا	///nhotogongitige= gengitice= \	DERWENT	2002/07/07 12:07
	3	, , , , , , , , , , , , , , , , , , , ,	USPAT; US-PGPUB;	2003/07/07 12:07
		<pre>benzopyran ) and ((photoacid acid) near generat\$3 ) and (resin resist photoresist ))</pre>	EPO; JPO;	
	İ	not ((IMAI-G IMAI-GENICHI EMAI-GENJI) and	DERWENT	
		benzopyran)		
		~~~~PJ + ~~~/	<u> </u>	

•			, <del> </del>	
	20	1 · · · · · · · · · · · · · · · · · · ·	USPAT;	2003/07/07 12:08
		benzopyran ) and (resin resist photoresist )	US-PGPUB;	
			EPO; JPO;	
			DERWENT	1 ( (
-	13	(((photosensitizer sensitizer ) same	USPAT;	2003/07/07 12:10
		benzopyran ) and (resin resist photoresist	US-PGPUB;	1
		)) not (((IMAI-G IMAI-GENICHI IMAI-GENJI)	EPO; JPO;	
		and benzopyran) (((photosensitizer	DERWENT	]
	ŀ	sensitizer ) same benzopyran ) and		
		((photoacid acid) near generat\$3 ) and		
	_	(resin resist photoresist )))		0000/05/05 10 10
-	0	jp-8334897-\$.did.	USPAT;	2003/07/07 12:10
			US-PGPUB;	İ
			EPO; JPO;	
		, annuan d 1'1	DERWENT	2002/07/07 12 06
-	2	jp-08334897-\$.did.	USPAT;	2003/07/07 12:26
•			US-PGPUB;	ł
			EPO; JPO;	
	_		DERWENT	0000/05/05 10 05
-	2	1 32	USPAT;	2003/07/07 12:27
		jp-2000056450	US-PGPUB;	•
			EPO; JPO;	
	_	/d= 11010000 0 4dd === 0000000000000000000000000	DERWENT	2002/07/07 12 07
-	6	(jp-11212252-\$.did. or jp-2000275823 or	USPAT;	2003/07/07 12:27
		jp-2000056450) jp-09138502-\$.did.	US-PGPUB;	
		jp-2000035665-\$.did.	EPO; JPO;	
			DERWENT	2000/05/05 10 10
-	2	jp-2000035665-\$.did.	USPAT;	2003/07/07 12:49
			US-PGPUB;	į
			EPO; JPO;	
	_		DERWENT	
-	2	titanocene same (\$5acid near generator)	USPAT;	2003/07/07 13:47
			US-PGPUB;	
			EPO; JPO;	
		4.1.	DERWENT	
-	1	1 1 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2	USPAT;	2003/07/07 13:47
		generator)	US-PGPUB;	
			EPO; JPO;	
		(4) (4)	DERWENT	0000/05/05 10 40
-	0		USPAT;	2003/07/07 13:48
		generator)) not (titanocene same (\$5acid	US-PGPUB;	
		near generator))	EPO; JPO;	
			DERWENT	2002/05/05
-	51	, ,	USPAT;	2003/07/07 14:24
		photoacid) near generator)	US-PGPUB;	
			EPO; JPO;	
		(magin magint shotomagint binday) and	DERWENT	2002/07/07 17 02
-	900	(resin resist photoresist binder) and	USPAT;	2003/07/07 17:03
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)	EPO; JPO;	
		//regin regist wheteresist hi-d	DERWENT	2002/07/07 14:05
-	509		USPAT;	2003/07/07 14:26
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)) and negative	EPO; JPO;	
	2808225	who has a washing a ward of a second of	DERWENT	2002/07/07 34 07
-	3797882	photocurable curable cur\$5 negative	USPAT;	2003/07/07 14:27
		crosslinkable crosslinked crosslink (cross	US-PGPUB;	
		adj link\$4) cross-link\$4	EPO; JPO;	
		///	DERWENT	2002/07/07 11 00
-	509	· · · · · · · · · · · · · · · · · · ·	USPAT;	2003/07/07 14:28
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)) and negative)	EPO; JPO;	
		and (photocurable curable cur\$5 negative	DERWENT	
		crosslinkable crosslinked crosslink (cross		
	43.600.55	adj link\$4) cross-link\$4)	HCD3m	2002/07/07 14 20
-	4167371		USPAT;	2003/07/07 14:30
		pre-bake\$4	US-PGPUB;	
			EPO; JPO;	
	1		DERWENT	

4553605	<pre>coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:31
- 1655136	irradiate irradiating expose exposure exposing exposed irradiated irradiation	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:31
- 1640490	develop development developing developed ]	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:32
- 360309	(visible adj light) "VIS"	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:32
- 57817	(dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:33
- 208	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed)) and ((visible adj light) "VIS"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:37
- 50		USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:41
27	•	USPAT; EPO; JPO; DERWENT	2003/07/07 15:48
	<pre>((visible adj light) "VIS"))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart) )</pre>	исрът.	2002/07/07 15:40
2	("6033826").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 15:48
- 1	(("6033826").PN.) and (generator) and (\$5sensitizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 16:31

		<u> </u>	T	
-	32	pyrene same (benzopyran)	USPAT; US-PGPUB;	2003/07/07 15:54
			EPO; JPO;	
			DERWENT	
-	18	(((((resin resist photoresist binder) and	USPAT;	2003/07/07 17:03
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)) and negative)	EPO; JPO; DERWENT	
		and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying	DEKWENI	
		applied coated spin-coated spin-coat (spin		
		adj (coated coat coating))) and (irradiate		
		irradiating expose exposure exposing exposed		
		irradiated irradiation ) and (develop		
		development developing developed ]) and ((visible adj light) "VIS"))) and (peel		
		peeling peelable peeled (peel\$4-apart)		
		(peel\$4 near apart) ) ) and ((visible VIS)		
•	_	near light)		
<del>-</del>	0	((((((resin resist photoresist binder) and	USPAT; US-PGPUB;	2003/07/07 17:02
		((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative)	EPO; JPO;	
	1	and ((dry drying heat-treat\$5 (heat\$5) bak\$4	DERWENT	
		pre-bake\$4) and (coat coating apply applying		
		applied coated spin-coated spin-coat (spin		
		adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed		
		irradiated irradiation ) and (develop		
		development developing developed ]) and		
		((visible adj light) "VIS"))) and (peel		
		peeling peelable peeled (peel\$4-apart)		
		(peel\$4 near apart) ) ) and ((visible VIS) near light)) and benzopyran		
_	0	1	USPAT;	2003/07/07 17:02
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)) and negative)	EPO; JPO;	
		and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying	DERWENT	
		applied coated spin-coated spin-coat (spin		
	:	adj (coated coat coating))) and (irradiate		
		irradiating expose exposure exposing exposed		
	:	irradiated irradiation ) and (develop development developing developed ]) and		
		((visible adj light) "VIS"))) and (peel		
		peeling peelable peeled (peel\$4-apart)		
		(peel\$4 near apart) ) ) and benzopyran		0000/05/05 05
-	2248	((visible adj light) "VIS") and benzopyran	USPAT; US-PGPUB;	2003/07/07 17:02
			EPO; JPO;	
		·	DERWENT	
-	395	, , , , , , , , , , , , , , , , , , ,	USPAT;	2003/07/07 17:03
	]	and ((visible VIS) near light)	US-PGPUB; EPO; JPO;	
			DERWENT	
-	293	(resin resist photoresist binder) and	USPAT;	2003/07/07 17:03
	į.	((((visible adj light) "VIS") and	US-PGPUB;	
		benzopyran) and ((visible VIS) near light))	EPO; JPO;	
<u>-</u>	21	((photoacid acid) near generat\$3 ) and	DERWENT USPAT;	2003/07/07 17:45
	21	((resin resist photoresist binder) and	US-PGPUB;	2005/07/07 17.45
		((((visible adj light) "VIS") and	EPO; JPO;	
		benzopyran) and ((visible VIS) near light)))	DERWENT	
-	1	ls-148	USPAT;	2003/07/07 18:04
			US-PGPUB; EPO; JPO;	
			DERWENT	
-	2	JP-11258798-\$.DID.	USPAT;	2003/07/07 18:04
			US-PGPUB;	
			EPO; JPO; DERWENT	
1	ĺ		DEKMENT	1

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-	2	benzopyran adj condensed adj ring	USPAT;	2003/07/08 11:34
			US-PGPUB;	
			EPO; JPO;	
•			DERWENT	
f -	7521	condensed adj ring	USPAT;	2003/07/08 11:53
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	0000/07/00 10 10
-	72	proliferating adj agent	USPAT;	2003/07/08 13:48
			US-PGPUB;	
			EPO; JPO; DERWENT	
	2661	sodium adj lamp	USPAT;	2003/07/08 12:09
_	2001	Soutum adj tamp	US-PGPUB;	2003/07/08 12:09
			EPO; JPO;	
			DERWENT	
_	120	(sodium adj lamp) same (nm wavlength)	USPAT;	2003/07/08 12:10
		(333334, 334, 334, 334, 344, 344, 344, 3	US-PGPUB;	
	·		EPO; JPO;	
			DERWENT	
_	72	proliferating adj agent	USPAT;	2003/07/08 14:31
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	jp-09138502-\$.did.	USPAT;	2003/07/08 13:50
			US-PGPUB;	
			EPO; JPO;	]
	_	(#C14000E#\ PM	DERWENT	2002/07/00 14 05
-	2	("6140025").PN.	USPAT;	2003/07/08 14:06
			US-PGPUB;	1
,			EPO; JPO; DERWENT	1
_	12	(proliferating adj agent ) and (resin resist	USPAT;	2003/07/08 14:09
	12	photoresist)	US-PGPUB;	2003/07/08 14:03
		photogodology	EPO; JPO;	
			DERWENT	
-	0	(proliferating adj agent) same ((fluidity	USPAT;	2003/07/08 14:35
		adj adjuster) (adhesion adj improver)	US-PGPUB;	
		(cissing adj inhibitor) (polymerization adj	EPO; JPO;	]
		inhibitor) pigment plasticizer)	DERWENT	1
-	134	(organic adj acid adj ester) same ((fluidity	USPAT;	2003/07/08 14:58
		adj adjuster) (adhesion adj improver)	US-PGPUB;	1
		(cissing adj inhibitor) (polymerization adj	EPO; JPO;	]
		inhibitor) pigment plasticizer)	DERWENT	2002/07/00 14 50
-	83	((organic adj acid adj ester) same	USPAT; US-PGPUB;	2003/07/08 14:58
		((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor)	EPO; JPO;	
		(polymerization adj inhibitor) pigment	DERWENT	
		plasticizer)) and (resist photoresist resin)		
_	79	((organic adj acid adj ester) same	USPAT;	2003/07/08 14:46
		((fluidity adj adjuster) (adhesion adj	EPO; JPO;	
		improver) (cissing adj inhibitor)	DERWENT	
		(polymerization adj inhibitor) pigment		
		plasticizer)) and (resist photoresist resin)		
-	2648	(organic adj acid adj ester)	USPAT;	2003/07/08 14:58
			US-PGPUB;	
			EPO; JPO;	
		(/	DERWENT	2002/07/00 3: 55
<del>-</del>	1070	((organic adj acid adj ester) ) and (resist	USPAT;	2003/07/08 14:59
·		photoresist resin)	US-PGPUB; EPO; JPO;	
			DERWENT	
_	834	((organic adj acid adj ester) ) and (resist	USPAT	2003/07/08 15:13
		photoresist resin)		=====================================
-	0	430.270.1.ccls.	USPAT	2003/07/08 15:00
-	2718	430/270.1.ccls.	USPAT	2003/07/08 15:09
-	5	430/270.1.ccls. and (((organic adj acid adj	USPAT	2003/07/08 15:01
		ester) ) and (resist photoresist resin))	1	
-	6		USPAT	2003/07/08 15:08
		ester) )		
	· · · · · · · · · · · · · · · · · · ·			

	T 1	(430/270.1.ccls. and ((organic adj acid adj	USPAT	2003/07/08 15:08
	1	ester) )) not (430/270.1.ccls. and		
		(((organic adj acid adj ester) ) and (resist		
		photoresist resin)))		
-	112	l <del>-</del>	USPAT	2003/07/08 15:11
_	5270		USPAT	2003/07/08 15:12
_		430/270.1.ccls. and (organic adj acid)	USPAT	2003/07/08 15:12
-	269		USPAT	2003/07/08 15:23
		(resist photoresist resin)		
	89		USPAT	2003/07/08 15:30
		and (resist photoresist resin)) and (visible		·
		near light)		
•	44	l	USPAT	2003/07/08 16:20
		and (resist photoresist resin)) and (visible		
		near light)) and negative		
	97	F =	USPAT	2003/07/08 16:21
		generator) and (photosensitizer sensitizer)		,
		and (visible near light)		
	155	IMAI-G IMAI-GENICHI IMAI-GENJI	USPAT;	2003/07/08 16:22
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
•	2		USPAT;	2003/07/08 16:33
		generator) and (photosensitizer sensitizer)	US-PGPUB;	
		and (visible near light)) and (IMAI-G	EPO; JPO;	
		IMAI-GENICHI IMAI-GENJI )	DERWENT	2002/07/00 16 22
-	2	("5801212").PN.	USPAT;	2003/07/08 16:33
			US-PGPUB;	
			EPO; JPO;	
	1		DERWENT	l i